



Ain Shams University  
University College for Women  
(Arts, Science, and Education)  
Physics Department

**PREPARATION AND CHARACTERIZATION  
OF NANOSTRUCTURE TRANSPARENT  
CONDUCTING OXIDE FILM  
( $\text{SnO}_2\text{: F}$ )**

**By**

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**(B.Sc.)**

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## *STATEMENT*

*Beside the work carried out in this thesis, the candidate attended post- graduate courses for one year in the following topics:*

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